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3	Inventor: Title: Assignee:	Methods For Forming Wor Interconnects, And Wordli Interconnect Structures Micron Technology, Inc.	al. rdlines, Transistor Gates, And Conducti ine, Transistor Gate, and Conductive	10525 U.S. P. 109/33271 109/33271 109/33271 109/33271 109/33271
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	11	6///99	Attorney: David G. Latwesen, Ph.I Reg. No. 38,533	5 .
	18 19 20 21	e:	Inventor: Klaus Florian Schuegr	af .
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Inventor: Randhir P. S. Thakur

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	AL	<u>[</u>	OTHER REFER	ENCES (including Author, Title, Date,	Pertinent Pages, Etc.)	L,			<u>L</u>			
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